

U.S. Application of FINK et al., Appln. No. 10/705,224
atty. dkt. 071469-0305806

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A baffle plate assembly for surrounding a substrate holder in a plasma processing system comprising:
a centering ring configured to be coupled to said substrate holder, wherein at least a portion of said centering ring extends radially outside a periphery of said substrate holder; and

a removable baffle plate comprising one or more passageways, wherein said baffle plate is configured to be centered within said plasma processing system by removably coupling said baffle plate to said portion of said centering ring extending radially outside said periphery of said substrate holder.

2. (Original) The baffle plate assembly of claim 1, wherein said centering ring is coupled to said substrate holder using fasteners.

3. (Original) The baffle plate assembly of claim 1, wherein said centering ring comprises a centering feature configured to center said baffle plate on said centering ring.

4. (Original) The baffle plate assembly of claim 3, wherein said centering feature comprises at least one of a centering pin, a centering receptacle, a centering edge, and radial face gear teeth.

5. (Original) The baffle plate assembly of claim 3, wherein said baffle plate comprises a mating feature configured to be coupled with said centering feature.

6. (Original) The baffle plate assembly of claim 5, wherein said mating feature comprises at least one of a centering pin, a centering receptacle, a centering edge, and radial face gear teeth.

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